

**AMENDMENTS TO THE CLAIMS**

Please amend the claims as follows:

1. (Currently amended) An electromagnetic wave shielding material which comprises a transparent substrate, physically developed nuclei laid thereon, and a layer of physically developed silver having a fine line pattern formed thereon, on said nuclei, and wherein the fine line pattern comprises a metal film plated upon physically developed metal silver nuclei deposited on the substrate on said physically developed silver.

2. (Original) The electromagnetic wave shielding material according to Claim 1, wherein the fine line pattern has a thickness of 15  $\mu\text{m}$  or less and a line width of 40  $\mu\text{m}$  or less, a total luminous transmittance of 50% or higher, and a surface resistance of 10  $\text{ohm}/\square$  or less.

3. (Previously presented) The electromagnetic wave shielding material according to Claim 2, wherein the total luminous transmittance is 60% or higher.

4. (Previously presented) The electromagnetic wave shielding material according to Claim 2, wherein the surface resistance is 7  $\text{ohm}/\square$  or less.

5. (Previously presented) The electromagnetic wave shielding material according Claim 2, wherein the thickness of the fine line pattern is 0.5 to 15  $\mu\text{m}$ .

6. (Previously presented) The electromagnetic wave shielding material according to Claim 5, wherein the thickness of the fine line pattern is 2 to 12  $\mu\text{m}$ .

7. (Previously presented) The electromagnetic wave shielding material according to Claim 2, wherein the line width of the fine line pattern is 1 to 40  $\mu\text{m}$ .

8. (Previously presented) The electromagnetic wave shielding material according to Claim 1, wherein the plating is an electrolytic plating.

9. (Previously presented) The electromagnetic wave shielding material according to Claim 1, wherein the plating is at least one kind of plating selected from copper and nickel.

10. (Currently amended) A process for preparing an electromagnetic wave shielding material which comprises ~~in order the steps of:~~

a) ~~exposing a light-sensitive material having a physical development nuclei layer and a silver halide emulsion layer on a transparent substrate in this order, with an optional fine line pattern,~~

b) ~~precipitating metal silver with a pattern having an~~ the optional fine line pattern ~~onto the physical development nuclei layer by physical development, then,~~

e) ~~removing any~~ a layer provided on the physical development nuclei layer, and

d) ~~subjecting to plating a metal with the use of onto~~ the physically developed metal silver ~~nuclei~~ as a catalytic nucleus to obtain an electromagnetic wave shielding material having a fine line pattern.

11. (Currently amended) The process for preparing an electromagnetic wave shielding material according to Claim 10, wherein the fine line pattern after the metal plating has a thickness of 15  $\mu\text{m}$  or less and a line width of 40  $\mu\text{m}$  or less, a total luminous transmittance of 50% or higher, and a surface resistance of 10  $\text{ohm}/\square$  or less.

12. (Previously presented) The process for preparing an electromagnetic wave shielding material according to Claim 11, wherein the total luminous transmittance is 60% or higher.

13. (Previously presented) The process for preparing an electromagnetic wave shielding material according to Claim 11, wherein the surface resistance is 7  $\text{ohm}/\square$  or less.

14. (Currently amended) The process for preparing an electromagnetic wave shielding material according to Claim 11, wherein after the metal plating the thickness of the fine line pattern is 0.5 to 15  $\mu\text{m}$ .

15. (Currently amended) The process for preparing an electromagnetic wave shielding material according to Claim 14, wherein after the metal plating the thickness of the fine line pattern is 2 to 12  $\mu\text{m}$ .

16. (Currently amended) The process for preparing an electromagnetic wave shielding material according to Claim 11, wherein after the metal plating the line width of the fine line pattern is 1 to 40  $\mu\text{m}$ .

17. (Previously presented) The process for preparing an electromagnetic wave shielding material according to Claim 10, wherein the plating is an electrolytic plating.

18. (Previously presented) The process for preparing an electromagnetic wave shielding material according to Claim 10, wherein the plating is at least one kind of plating selected from copper and nickel.

19. (Previously presented) The process for preparing an electromagnetic wave shielding material according to Claim 18, wherein an electrolytic plating is carried out by dipping a transparent substrate on which a physically developed silver has been formed in a bath containing copper sulfate and sulfuric acid as main components with a current density of 1 to 20  $\text{ampere}/\text{dm}^2$  at 10 to 40°C.